

Electron Beam Focusing of ~1.5 GeV Laser Plasma Accelerators for High Capture Efficiency Staging

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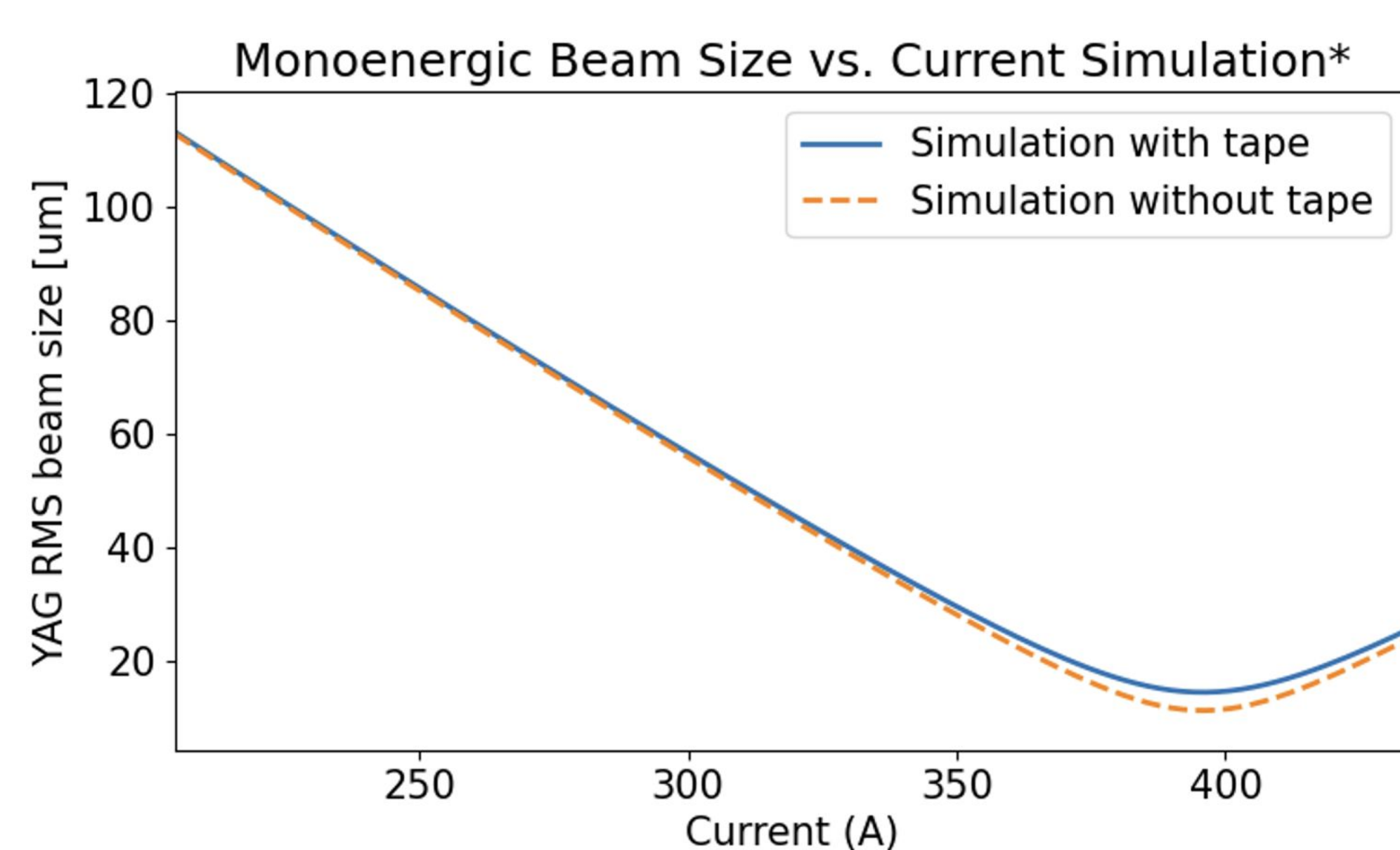
Introduction

- Laser-plasma accelerator (LPA) staging:
 - Couples 2+ LPAs
 - Overcomes laser depletion and increases the electron beam energy
 - Applicable for future multiple-staged high-energy particle colliders and high average power khz-class LPA concepts[1], [3]
- Precision e-beam focusing critical for high charge coupling efficiency between stages
- Advantages of Active Plasma Lenses (APLs) [2] in LPA staging: strong focus over ~ cm scales, single-element, tunable, radially symmetric focusing [4]

Here we present results from using an APL to focus GeV beams over cm scales for staging

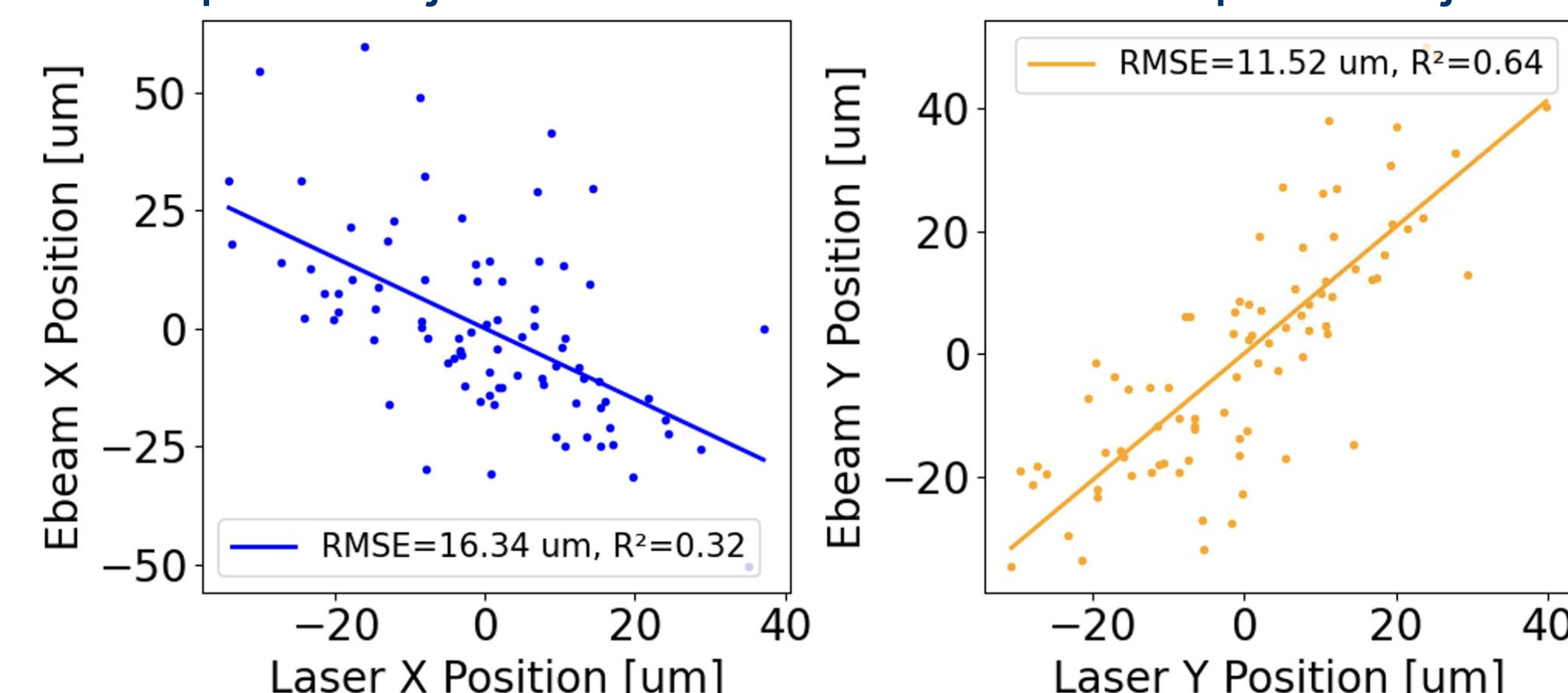
Use of 25 μm thick tape is a small factor in larger focused spot size

- Tape plasma mirror scatters electron beams and causes some emittance growth [6]
- Energy spread is small factor in higher beam size; simulations* of rms beam sizes show:
 - At min $\Delta E/E=3\%$, beam size = 15.6 μm
 - At typical $\Delta E/E=8\%$, beam size = 16.8 μm
 - At worst $\Delta E/E = 18\%$, beam size = 17.6 μm

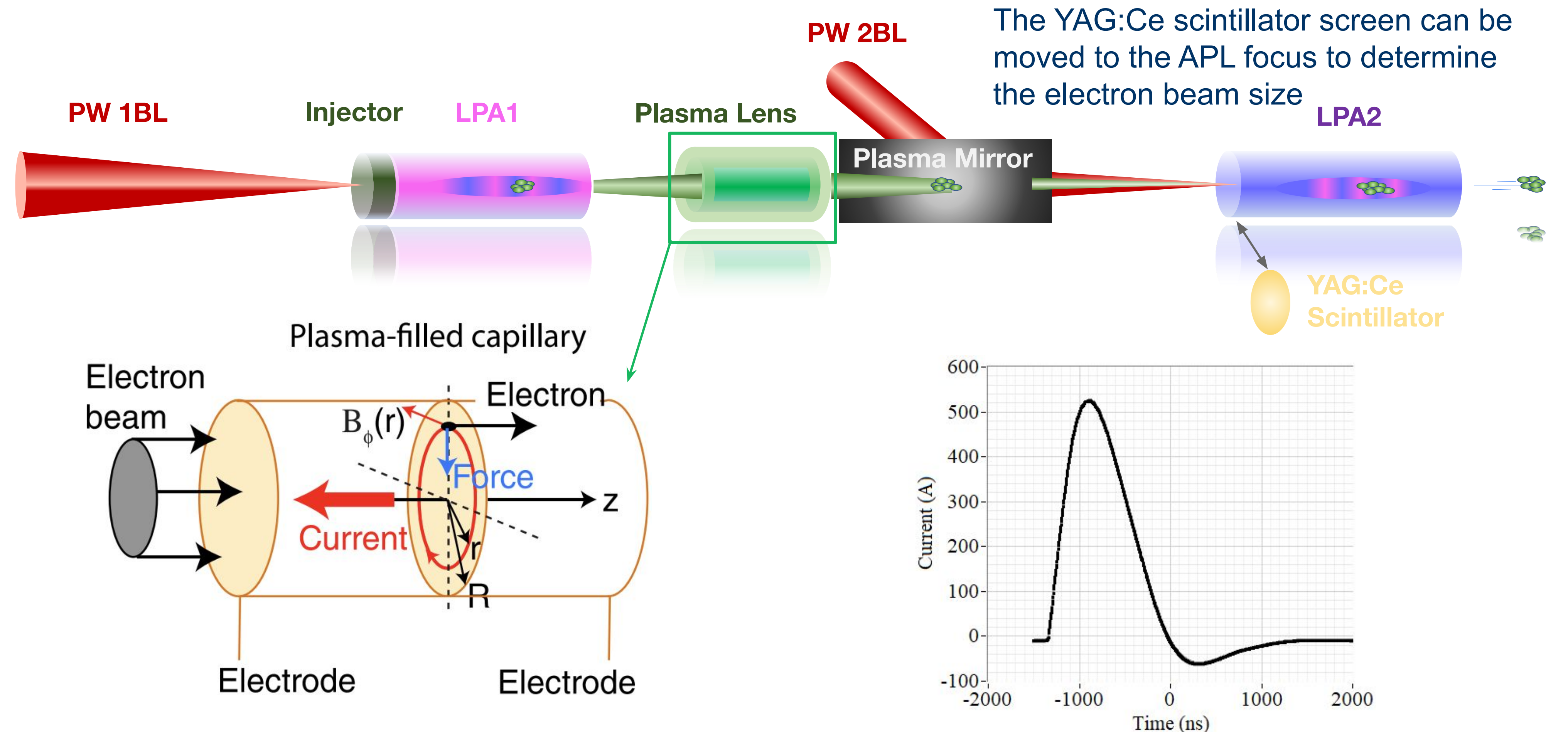


Transverse electron beam position control needed for effective staging

Laser position jitter correlated with electron position jitter



Experimental layout: APL focuses beam from LPA1 to plasma mirror



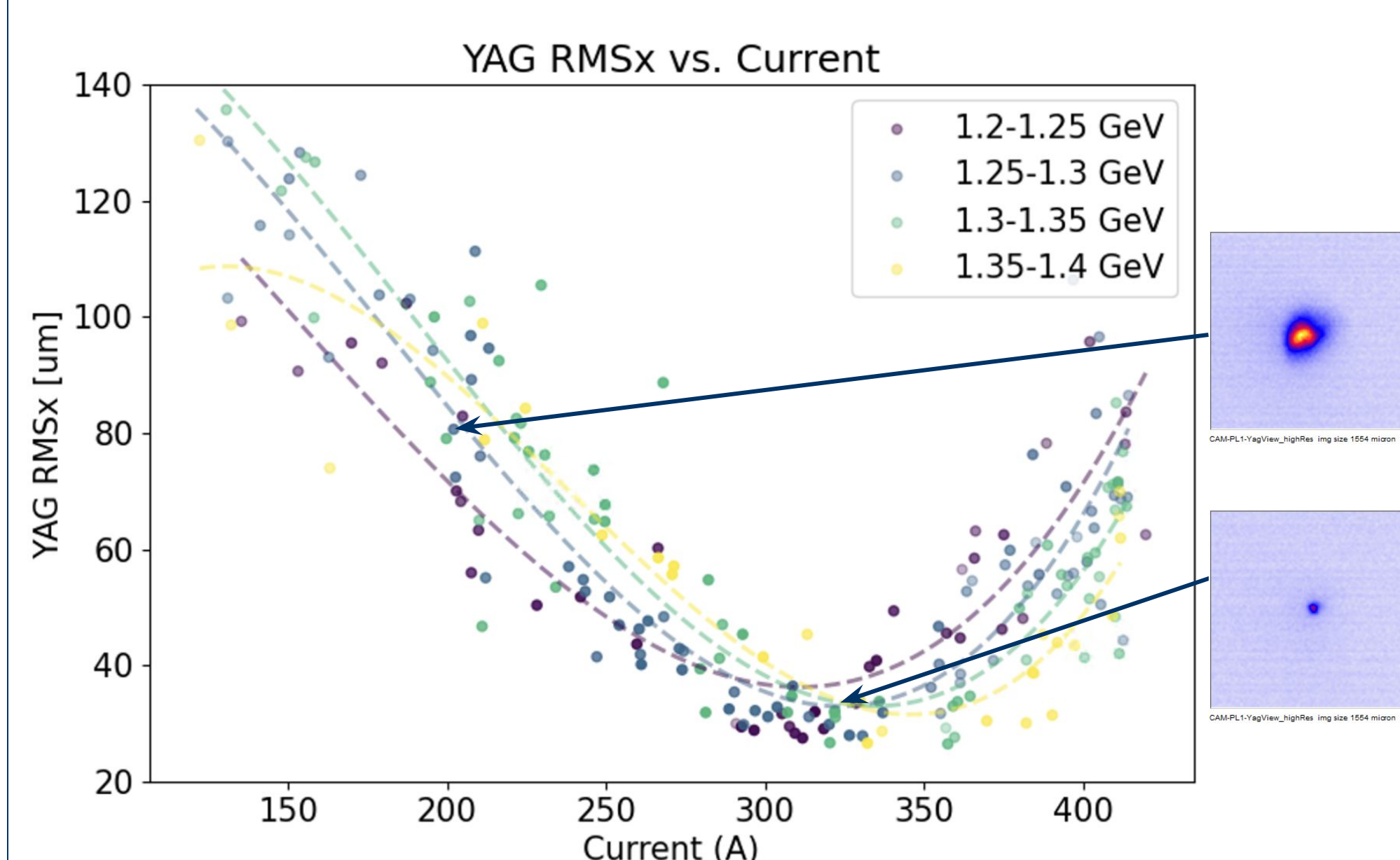
Schematic of the focusing force in an APL. From Figure 1(a) of [4]

Current trace example for the APL discharge. Jitter of 200 shots $\pm$ 2 A

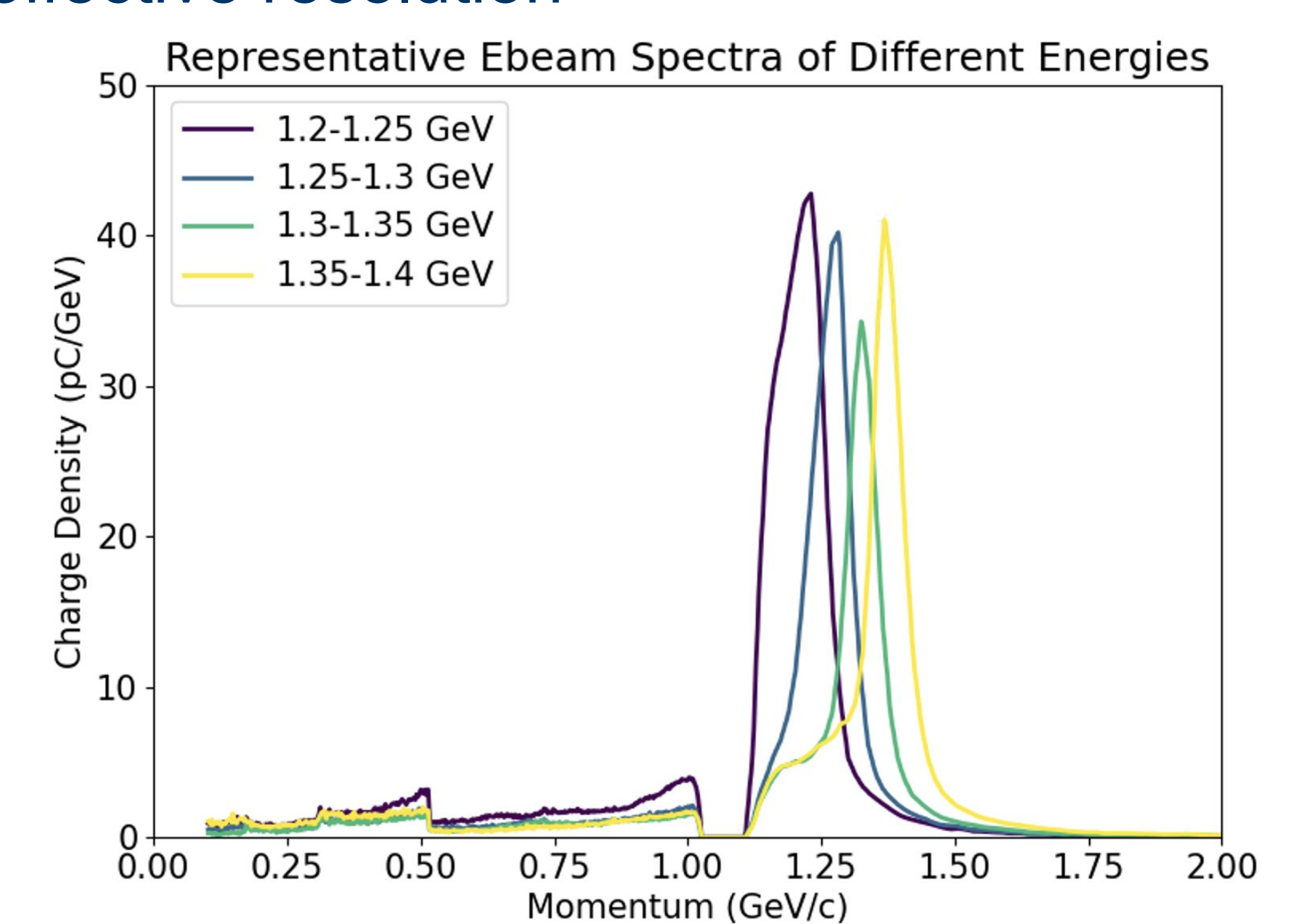
- APL used Argon for mitigating emittance growth [5]
- Delay between laser arrival time and current peak determines the electron beam focus strength

Electron beam size sensitive to electron energy by ~ 25 μm at 330 A

- Minimum beam size $\approx$ 25 μm rms at 330 A
 - $\lambda_p (\mu\text{m}) \approx 3.3 \times 10^{10} / (n_0 (\text{cm}^{-3}))^{1/2}$
 - $\approx$ 100 μm for $n_0 = 10^{17} \text{ cm}^{-3}$
- At 330 A, electron energy jitter changes electron beam size by ~ 25 μm RMS
- High opacity = low variance about optimum electron energy at each current



- We can simultaneously measure the electron beam spectrum and focus spot size
- Electron beam energy after 1st stage determines APL focal length
- Optical resolution of the YAG is 2 μm
- YAG:Ce screen is 100 μm thick but depth of field of imaging system ~ 10 μm , limiting effective resolution



Next Steps

- Use the APL in future LPA staging
- Develop laser transverse jitter stabilization for transverse electron beam control in staging
- Replace plasma mirror tape with liquid crystal

* Simulation parameters: 1.3 GeV electrons, uniform APL current density, 5 μm sized 0.3 mrad divergence beam at the first stage, 10 μm quadrature for YAG resolution

References

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